

ABSTRACT

ETCHANT COMPOSITION

In one aspect, provided is an etchant composition with high storage stability.

An aspect of the present disclosure relates to an etchant composition for etching of a layer to be etched that contains at least one metal. The etchant composition contains a nitric acid, a polyamine with a number average molecular weight of 300 or more, a nitrogen-containing basic compound with a molecular weight of less than 300, and water.